IN THE SPECIFICATION:

On page 2 and continuing on page 3, please amend the following paragraph:

"Because microlithography exposure lenses are very sensitive to chromatic ~~abberations~~ aberration of the light source, it is required that the laser produce light with very narrow spectrum line width. For example, state of the art excimer lasers are now producing spectral linewidths on the order of 0.5 pm as measured at full width at half maximum values and with 95% of the light energy concentrated in the range of about 1.5 pm. New generations of microlithography exposure tools will require even tighter spectral requirements. In addition, it is very important that the laser central wavelength be maintained to very high accuracy as well. In practice, it is required that the central wavelength is maintained to better than 0.05 – 0.1 pm stability."